EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	986	(HF or hydrofluoric) same ("NH.sub.3" or ammonia) same ("SiO.sub.2" or "silicon dioxide" or insulating or dielectric)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:54
L3	475	(HF or hydrofluoric) same ("NH.sub.3" or ammonia) same ("SiO.sub.2" or "silicon dioxide")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:47
L4	2	"20020063110"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:47
L6	29	(HF or hydrofluoric) same ("NH.sub.3" or ammonia) same ("SiO.sub.2" or "silicon dioxide" or insulating or dielectric) same "etch rate"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:53
L7	230	(HF or hydrofluoric) same ("NH.sub.3" or ammonia) same ("SiO.sub.2" or "silicon dioxide" or insulating or dielectric) same plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:54
L8	6201	((438/706) or (438/710) or (438/714)).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:54
L9	14061	(HF or hydrofluoric) and ("NH.sub.3" or ammonia) and ("SiO.sub.2" or "silicon dioxide" or insulating or dielectric) and (etch$4 or remov$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:55

L10	189	8 and 9	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:55
L11	127	hasebe-kazuhide.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 12:55